

SUPPORT FOR THE AMENDMENTS

Newly-added Claims 13-30 are supported by the specification and the original claims.
No new matter is believed to have been added to the present application by the amendments submitted above.

REMARKS

Claims 13-30 are pending. Favorable reconsideration is respectfully requested.

The present invention relates to a process for producing high-purity silicon, comprising thermally decomposing a gas phase mixture comprising monosilane and a monochlorosilane, and depositing massive silicon. See Claim 13.

The rejections of the claims under 35 U.S.C. §102(b) and §103(a) over JP 2001-064774 (JP '774) are respectfully traversed. JP '774 fails to disclose or suggest the claimed process.

JP '774 describes a process for depositing a silicon thin film. See the Title and Abstract of the reference. See also Claim 2, which describes formation of a thin film. In the only Example of the reference, a film having a thickness of 1 μ m was formed. See the bottom of page 7 of 8.

In contrast, the process of the present invention provides for massive silicon deposition. Thus, in the Example of the present application a layer of silicon having a thickness of 2.8 mm was produced.

Accordingly, the claimed process produces silicon produces a much-thicker silicon product as compared to the process described by JP '774. For that reason, the reference fails to anticipate the claimed process.

Moreover, JP '774 is explicit about the formation of a silicon thin film. There is no motivation in that reference to modify the process described in the reference to deposit massive silicon as claimed, since doing so would be contrary to the explicit teachings of the reference. Accordingly, JP '774 fails to suggest the claimed process.

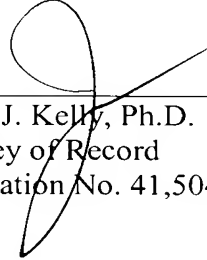
In view of the foregoing, the claimed process is neither anticipated by nor obvious over JP '774. Accordingly, withdrawal of these grounds of rejection are respectfully requested.

The rejection of the claims under 35 U.S.C. §112, second paragraph, is believed to be obviated by the amendments submitted above. Accordingly, Applicants submit that the claims are definite within the meaning of 35 U.S.C. §112, second paragraph. Withdrawal of this ground of rejection is respectfully requested.

Applicants submit that the present application is in condition for allowance. Early notice to this effect is earnestly solicited.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.

A handwritten signature in black ink, appearing to be 'James J. Kelly', is written over a horizontal line.

James J. Kelly, Ph.D.
Attorney of Record
Registration No. 41,504

Customer Number

22850

Tel: (703) 413-3000
Fax: (703) 413 -2220
(OSMMN 08/07)